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19 -Pulsed-Target Magnetron-Enhanced ICP Plasma System

Tuesday 4 June 2019 16:55 (2 minutes)

In this poster we present a new pulsed-target magnetron-enhanced plasma system, with applications in plasma materials processing and fundamental plasma physics. This system embeds a high-density magnetron discharge within a relatively uniform medium-density Inductively Coupled Plasma (ICP). We report on experimental studies of this unique plasma system using an RF-compensated Langmuir probe for plasma density and electron temperature measurements, as well as a high-speed camera to capture rapidly moving plasma structures. Preliminary modelling results using the VSim PIC simulation code will also be presented.

Authors: CHANG, Alex (University of Saskatchewan Plasma Physics Lab); KHODAEE, Ayub (University of Saskatchewan Plasma Physics Lab); MORENO, Joel (University of Saskatchewan Plasma Physics Lab); Prof. COUEDEL, Lenaic (University of Saskatchewan Plasma Physics Lab); Prof. BRADLEY, Michael (University of Saskatchewan Plasma Physics Lab)

Presenter: CHANG, Alex (University of Saskatchewan Plasma Physics Lab)

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